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--As is clear from FIG. 5, in the ultrapure water supply system cleaned by the cleaning methods according to Examples 1 to 3, the number of fine particles in the ultrapure water produced by the system dropped to a level lower than an allowable upper-limit value (1/mL) before a whole day passed since the start of operation of the system following the completion of the cleaning. Namely, the cleaning methods of Examples 1 to 3 proved to have high fine particles removing capability. On the other hand, in the system cleaned by the method according to Comparative Example 1, more than eight days were required for the number of fine particles in the ultrapure water produced by the system to drop to a level lower than the allowable upper-limit value, and thus, it was found that the cleaning method of Comparative Example 1 had poor fine particle removing capability.--

Page 23, lines 11-23, ~~replace~~ the original paragraph with the following paragraph:

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--Also as seen from FIG. 6, in Examples 1 to 3, the time required for the TOC of the ultrapure water produced by the system to drop to a level lower than an allowable upper-limit value (1 µg/L) was shorter than a whole day as counted from the start of operation of the system, proving that the cleaning methods of Examples 1 to 3 also have excellent organic matter removing capability. On the other hand, in Comparative Example 1 it took four to five days for the TOC to decrease to a level

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lower than the allowable upper-limit value, and it was found that the cleaning method of Comparative Example 1 had poor organic matter removing capability.--

IN THE CLAIMS:

Please ~~amend~~ the following claims:

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6. (Amended) The cleaning method according to claim 2, wherein the basic solution is an aqueous solution of ammonia or ammonium salt, or an aqueous solution of alkali metal hydroxide, or a mixture of the aqueous solution of ammonia or ammonium salt and the aqueous solution of alkali metal hydroxide.

7. (Amended) The cleaning method according to claim 2, wherein the basic solution is pure water or ultrapure water in which alkaline gas is dissolved.

Please ~~add~~ the following claims 8-11:

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8. (New) The cleaning method according to claim 4, wherein the basic solution is an aqueous solution of ammonia or ammonium salt, or an aqueous solution of alkali metal hydroxide, or a mixture of the aqueous solution of ammonia or ammonium salt and the aqueous solution of alkali metal hydroxide.